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Erratum: "Ion-channeling analysis of boron clusters in silicon" [J. Appl. Phys. 90, 4741 (2001)]

Selen, L. J. M. ; Janssen, F. J. J. ; van IJzendoorn, L. J.; de Voigt, M. J. A. ; Theunissen, M. J. J. ; Smulders, P. J. M.; Eijkemans, T. J.

Published in:
Journal of Applied Physics

DOI:
[10.1063/1.1463446](https://doi.org/10.1063/1.1463446)

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Document Version
Publisher's PDF, also known as Version of record

Publication date:
2002

[Link to publication in University of Groningen/UMCG research database](#)

Citation for published version (APA):

Selen, L. J. M., Janssen, F. J. J., van IJzendoorn, L. J., de Voigt, M. J. A., Theunissen, M. J. J., Smulders, P. J. M., & Eijkemans, T. J. (2002). Erratum: "Ion-channeling analysis of boron clusters in silicon" [J. Appl. Phys. 90, 4741 (2001)]. *Journal of Applied Physics*, 91(8). <https://doi.org/10.1063/1.1463446>

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Citation: [Journal of Applied Physics](#) **91**, 5507 (2002); doi: 10.1063/1.1463446

View online: <https://doi.org/10.1063/1.1463446>

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[DOI: 10.1063/1.1463446]

The title of the paper should have been: “Ion channeling for strain analysis in buried nanofilms (<6 nm).” In addition, three references appeared incorrectly; corrected versions of Refs. 1, 7, and 13 follow:

¹B. D. Cullity, *Elements of X-Ray Diffraction* (Addison-Wesley, Reading, MA, 1976).

⁷T. C. Q. Noakes, P. Baily, P. K. Hucknall, K. Donovan, and M. A. Howson, *Phys. Rev. B* **58**, 4934 (1998).

¹³J. Lindhard and K. Dan., *Vidensk. Selsk. Mat. Fys. Medd.* **1965**, 34.

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